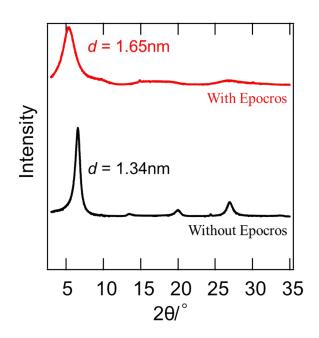
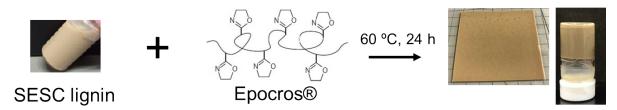
## Supporting Information

Title Non-flammable UV protection films consisting of clay and lignin with tunable light/gas transparency

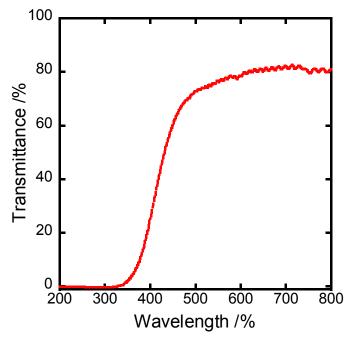
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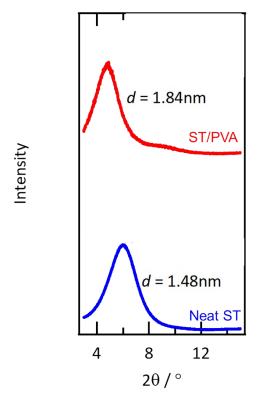
**Fig. S1**. X-ray diffraction (XRD) pattern of clay-lignin films consisting of MMT and SESC lignin without Epocros® (lower, MMT:SESC lignin = 8:2 w/w%) or with Epocros® (upper, MMT:SESC lignin: Epocros® = 7:2:1 w/w%). The lowest  $2\theta$  peak (the basal (001) reflection of the MMT) shifted to a smaller  $2\theta$  region after the addition of Epocros®. The  $2\theta$  peak of MMT was unaffected by the addition of SESC lignin, i.e., SESC lignin does not insert into MMT interlayers.<sup>S1</sup> Thus, Epocros® inserts between the MMT platelets. The XRD patterns were collected using a Rigaku Smart Lab X-ray diffractometer using Cu K $\alpha$  radiation, a Cu K $_{\beta}$  filter, a 2.5° Soller slit, and a nonreflecting rotation stage. The collected count range was 2–20°  $2\theta$  in 0.02°  $2\theta$  increments.



**Fig. S2** Typical crosslinking reaction between SESC lignin and Epocros®. Here, the hydroxyl groups in lignin and the oxazoline groups in Epocros® form covalent bonds.<sup>S2</sup> This crosslinking reaction between SESC lignin and Epocros® in their water dispersion causes the gelation of the SESC lignin and Epocros® mixture (SESC lignin:Epocros® = 1:1 w/w%), as shown in right photos.



**Fig. S3** Typical UV-vis spectrum of clay-lignin films consisting of ST and SESC lignin (ST: SESC lignin = 80:20 w/w%)



**Fig. S4**. XRD pattern of clay-lignin films consisting of ST and SESC lignin with PVA (upper, ST:PVA:SESC lignin = 76:19:5 w/w%) and neat ST (lower). The lowest  $2\theta$  peak (the basal (001) reflection of the ST) shifted to a smaller  $2\theta$  angle by the addition of PVA. As shown in Fig. S1, the  $2\theta$  peak was unaffected by the addition of SESC lignin. Thus, the PVA intercalates into ST interlayer.

## REFERENCES

S1 K. Shikinaka, M. Nakamura, R. R. Navarro and Y. Otsuka, Green Chem., 2019, 21, 498.

S2 K. Takahashi, R. Ishii, T. Nakamura, A. Suzuki, T. Ebina, M. Yoshida, M. Kubota, T. T. Nge and T. Yamada, *Adv. Mater.* 2017, **29**, 1606512.